



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/388,826
Filing Date September 1, 1999
Inventor..... Weimin (Michael) Li et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner E. Kielin
Attorney's Docket No. MI22-1208
Title: Low k Interlevel Dielectric Layer Fabrication Methods

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References -See Attached Form PTO-1449

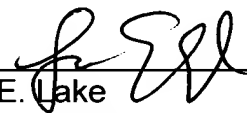
In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the references which are listed on the attached Form PTO-1449, copies of which are attached.

No admission is made regarding whether all the submitted references are prior art.

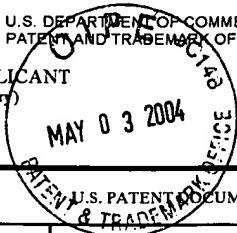
Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated: 03 May 2004

By: 
James E. Lake
Reg. No. 44,854

| | | | | | | | |
|---|--|--|--|----------------------------------|--|--------------------------|--|
| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE | | ATTY. DOCKET NO. MI22-1208 | | SERIAL NO. 09/388,826 | |
| LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) | | | | APPLICANT Weimin Li, et al. | | | |
| | | | | FILING DATE September 1, 1999 | | GROUP 2813 | |



| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
|-------------------|-----------------|-----------|---------|---------------|----------|----------------------------|
| | AA | 5,985,519 | 11/1999 | Kakamu et al. | | |
| | AB | 5,747,388 | 05/1998 | Kusters et al | | |
| | AC | 5,639,687 | 06/1997 | Roman et al | | |
| | AD | 5,498,555 | 03/1996 | Lin | | |
| | AE | 6,153,504 | 11/2000 | Shields et al | | |
| | AF | 4,971,655 | 11/1990 | Stefano et al | | |
| | AG | 6,498,084 | 12/2002 | Bergemont | | |
| | AH | 5,036,383 | 07/1991 | Mori | | |
| | AI | | | | | |
| | AJ | | | | | |
| | AK | | | | | |
| | AL | | | | | |

| FOREIGN PATENT DOCUMENTS | | | | | | | |
|--------------------------|------------|---------|-------|----------|-------------|----|--|
| Document Number | Date | Country | Class | Subclass | Translation | | |
| | | | | | Yes | No | |
| AM | 6232113 | 08/1994 | Japan | | | | |
| AN | 8051058 | 02/1996 | Japan | | | | |
| AO | 63316476 | 12/1988 | Japan | | | | |
| AP | 8078322 | 03/1996 | Japan | | | | |
| AQ | 10-163083 | 06/1998 | Japan | | | | |
| AR | 08-045926A | 02/1996 | Japan | | | | |

| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | |
|---|--|--|--|
| AS | | | |
| AT | | | |

| | |
|----------|-----------------|
| EXAMINER | DATE CONSIDERED |
|----------|-----------------|

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

| | | | | | | |
|---|-----------------|---|----------------------------------|-------------------------------|--------------------------|----------------------------|
| Form PTO-1449 | | U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE <div style="border: 1px solid black; border-radius: 50%; padding: 5px; display: inline-block;"> RECEIVED MAY 03 2004 PATENT & TRADEMARK OFFICE </div> | | ATTY. DOCKET NO. MI22-1208 | SERIAL NO. 09/388,826 | |
| LIST OF ART CITED BY APPLICANT (Use several sheets if necessary) | | | | | | |
| | | | APPLICANT Weimin Li, et al. | | | |
| | | | FILING DATE September 1, 1999 | GROUP 2813 | | |
| PATENT AND TRADEMARK DOCUMENTS | | | | | | |
| *Examiner Initial | Document Number | Date | Name | Class | Subclass | Filing Date If Appropriate |
| | AA | 6,503,818 B1 | 01/2003 | Jang | | |
| | AB | 6,486,061 B1 | 11/2002 | Xia et al. | | |
| | AC | 6,486,057 B1 | 11/2002 | Yeh et al. | | |
| | AD | 6,465,372 B1 | 10/2002 | Xia et al. | | |
| | AE | 6,444,593 B1 | 09/2002 | Ngo et al. | | |
| | AF | 6,436,808 B1 | 08/2002 | Ngo et al. | | |
| | AG | 6,435,943 B1 | 08/2002 | Chang et al. | | |
| | AH | 6,429,115 B1 | 08/2002 | Tsai et al. | | |
| | AI | 6,284,677 B1 | 09/2001 | Hsiao et al. | | |
| | AJ | 6,030,901 | 02/2000 | Hopper et al. | | |
| | AK | 6,133,618 | 10/2000 | Steiner | | |
| | AL | 5,994,217 | 11/1999 | Ng | | |
| FOREIGN PATENT DOCUMENTS | | | | | | |
| | Document Number | Date | Country | Class | Subclass | Translation Yes No |
| | AM | 8046186 | 02/1996 | Japan | | |
| | AN | 8046186 | 2/1996 | Japan | | X |
| | AO | 7201716 | 08/1995 | Japan | | |
| | AP | 7201716 | 08/1995 | Japan | | X |
| | AQ | 8046188 | 02/1996 | Japan | | |
| OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | |
| | AR | Wolf, S., Silicon Process., V.1 407-413. | | | | |
| | AS | Wolf, S., Silicon Process., Vol. 2 48-49 and 435. | | | | |
| | AT | Wolf, S., Silicon Processing for the VLSI Era, Vol. 3, page 635. | | | | |
| EXAMINER | | | | DATE CONSIDERED | | |
| *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. | | | | | | |